



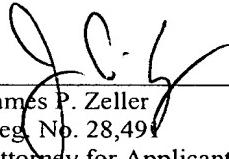
JFW

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants: Young Sun Hwang et al.)
Serial No.: 10/719,083)
Filed: November 21, 2003)
For: Methods for Forming Fine)
Photoresist Patterns)
Group Art Unit: 1765)
Examiner: Patricia Ann George)
Confirmation No. 2261)
)

I hereby certify that this paper and the
documents referred to as enclosed
therewith are being deposited with the
United States Postal Service as first class
mail, postage prepaid, on **January 23,**
2007, in an envelope addressed to MS
Amendments, Commissioner for Patents,
P.O. Box 1450, Alexandria, Virginia
22313-1450



James P. Zeller
Reg. No. 28,491
Attorney for Applicant

AMENDMENT "C"

MS Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, Virginia 22313-1450

Dear Sirs:

Please amend this application as follows:
the amendment to the claims section (along with a complete listing of
claims) begins on page 2 of this paper;
the remarks section begins on page 4 of this paper.